

Configurational reorganization of bistable defects in semiconductors

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The accumulation of the metastable state and the ground state of a bound electron in two different configurations of a bistable defect has been analyzed. The results are compared with experiment.

Time-dependent capacitive spectroscopy has revealed defects in semiconductors which have two or more configurational states of a bound electron.^{1–4} In particular, Kuchinskiĭ *et al.*⁶⁴ observed a bistable defect in γ -bombarded *n*-type zone-refined silicon with metastable and ground states characterized by thermal-ionization energies $E_t = 0.12$ eV and $E_t = 0.18$ – 0.19 eV, respectively. Kuchinskiĭ *et al.* suggested two

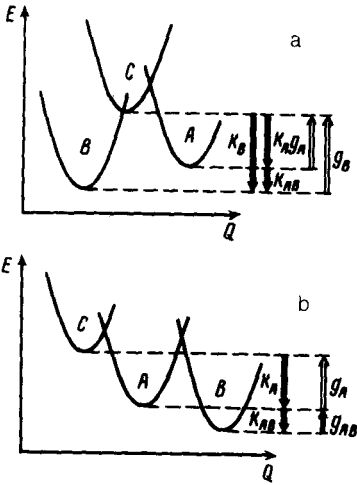


FIG. 1. Configuration diagrams of a bistable defect.

possible configurations of this defect, without giving preference to either. In the present letter we show that the question of the configuration of a bistable defect can be resolved by studying how the concentration of the ground state of a defect varies with the time over which it is filled by electrons. We will compare theoretical and experimental results for proton-bombarded silicon.

Figure 1, a and b, shows the two possible configuration diagrams of a three-level system of a bistable defect, according to Kuchinskii *et al.*⁴ Shown here are the electronic transitions which result in the transition of the defect from the state of a free electron (*C*) to a metastable state (*A*) or the ground state (*B*) of a bound electron, and vice versa, during charge exchange. On the basis of the relative positions of the various states of the defect along the configuration coordinate *Q* it can be asserted that for the first diagram (Fig. 1a) the transitions *C*→*A*, *C*→*B*, and *A*→*B* occur, with probabilities characterized by the coefficients k_A , k_B , and k_{AB} , respectively. Because of the high energy barrier for the *A*→*B* transition, the conditions $k_A, k_B > k_{AB}$, should hold. For the second diagram (Fig. 1b), the *C*→*B* transitions are improbable and can be ignored, while the relation between the coefficients k_A and k_{AB} is unknown.

In the method of time-varying capacitive spectroscopy of semiconductors, one measures the concentrations of the states of a bound electron, $N_A(t)$ and $N_B(t)$, which accumulate during a filling pulse *t*, in the stage of the thermal ionization of the electrons. The coefficients for the thermal ionization of the electrons, $g \sim \exp(-E_t/kT)$, or the thermal-ionization energy E_t are characteristics of the states which become freed of electrons.

Let us examine in detail the changes in the states of a bistable defect during the action of the filling pulse. This process can be described by a phenomenological theory of electronic transitions, according to which the following system of kinetic equations holds for the concentrations of free electrons, $N_C(t)$, and of bound electrons:

$$\frac{dN_C}{dt} = -k_A N_C \{-k_B N_C\}; \quad \frac{dN_A}{dt} = k_A N_C - k_{AB} N_A; \quad \frac{dN_B}{dt} = k_{AB} N_A \{+k_B N_C\}, \quad (1)$$

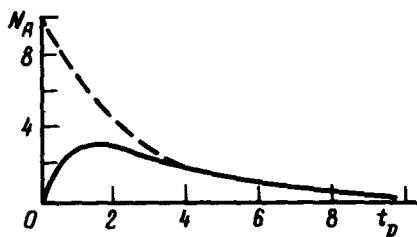


FIG. 2. Concentration of a metastable state versus the duration of the filling pulse.

The braces (curly brackets) contain terms which must be eliminated if the transitions that occur are those in Fig. 1b.

A solution of equations (1) under the conditions $N_C(0) = N$, where the right side is the total concentration of defects, and $N_A(0) = N_B(0) = 0$, is¹⁾

$$N_A(t)/N = \frac{k_A}{k_1 - k_{AB}} [\exp(-k_{AB}t) - \exp(-k_1 t)]; \quad (2)$$

$$N_B(t)/N = \frac{k_A}{k_1 - k_{AB}} [1 - \exp(-k_{AB}t)] + \frac{k_2}{k_1 - k_{AB}} [1 - \exp(-k_1 t)], \quad (3)$$

where we have $k_1 = k_A + k_B$ and $k_2 = k_B - k_{AB}$ for the first scheme of electronic transitions (Fig. 1a) and $k_1 = k_A$, $k_2 = -k_{AB}$ for the second scheme (Fig. 1b). We are assuming $k_1 \neq k_{AB}$.

It can be seen from expression (2) that the curve of the concentration of the metastable state, $N_A(t)$, versus the time over which the filling pulse operates, t , has the same shape (the solid line in Fig. 2) for various schemes of the electronic transitions. The curve of $N_B(t)$, in contrast, differs for the different schemes (the solid lines in

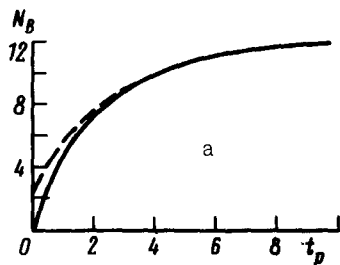


FIG. 3. Concentration of the ground state versus the duration of the filling pulse.

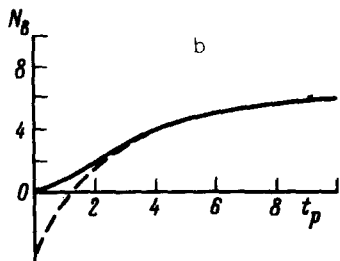


Fig. 3, a and b), since there are opposite signs (in the case $k_B > k_{AB}$) on the second term in expression (3). The dashed lines in Figs. 2 and 3 are plots of Eqs. (2) and (3) under the condition $\exp(-k_1 t) = 0$. Under the conditions $t \approx k_{AB}^{-1} \gg k_1^{-1}$, the curves shown by the solid and dashed lines coincide, and this circumstance can be utilized to determine k_{AB} during the analysis of experimental data.

We have used the expressions derived here, (2) and (3), to study a bistable radiation-induced defect in *n*-type zone-refined silicon. Samples with a resistivity $\sim 80 \Omega \cdot \text{cm}$ were bombarded with protons with an energy of 7.8 or 100 MeV. As in the case of γ -ray bombardment,⁴ we observed two states of a defect, with thermal-ionization energies $E_i = 0.13 \pm 0.01$ eV and $E_i = 0.20 \pm 0.02$ eV. The length of the filling pulse was varied over the interval $t_p = 0.1\text{--}100 \mu\text{s}$. It was found that the concentration of the $E_i = 0.13$ -eV states varies as a function of t in accordance with expression (2). This state is therefore metastable. The behavior of the concentration of the $E_i = 0.20$ -eV state as a function of t is described by expression (3), which describes the formation of the ground state of a defect for the first configuration diagram (Fig. 1a). The coefficient which characterizes the reorganization from the metastable state to the ground state is an exponential function of the temperature: $k_{AB} = \nu \exp(-E_{AB}/kT)$, where $\nu = 1.4 \times 10^{12} \text{ s}^{-1}$, and $E_{AB} = 0.15$ eV.

In summary, theoretical expressions (2) and (3) can be compared with experimental data to reveal qualitative and quantitative characteristics of a bistable defect.

¹The initial conditions correspond to a large repetition period of the filling pulses in an experiment: $t_f \gg g^{-1}$.

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